

Docket No.: 210136US99

OBLON
SPIVAK
MCCLELLAND
MAIER
NEUSTADT
P.C.

ATTORNEYS AT LAW

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

RE: Application Serial No.: 09/901,109

Applicants: Ravindranath DROOPAD, et al.

Filing Date: July 10, 2001

For: STRUCTURE AND METHOD FOR FABRICATING SEMICONDUCTOR STRUCTURES AND DEVICES UTILIZING THE FORMATION OF A COMPLIANT SUBSTRATE COMPRISING AN OXYGEN-DOPED

COMPOUND SEMICONDUCTOR LAYER

Group Art Unit: 2815
Examiner: BAUMEISTER

SIR:

Attached hereto for filing are the following papers:

RESTRICTION RESPONSE; REQUEST FOR EXTENSION OF TIME (two-month)

Our check in the amount of \$410.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPRAK, McCLELLAND, MAIER & NEOSTADT, P.C.

Richard L. Treanor Registration No. 36,379 RECEIVED

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HNOLOGY CENTER 28

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(703) 413-3000 (phone) (703) 413-2220 (fax)